BAY AREA AIR QUALITY MANAGEMENT DISTRICT
Best Available Control Technology (BACT) Guideline

Source Category

Source:	***Semiconductor Fabrication - Photoresist Operations***	Revision:	***2***
		Document #:	***149A.1.1***
Class:	***All***	Date:	***06/16/95***

Determination

POLLUTANT	BACT 1. Technologically Feasible/ Cost Effective 2. Achieved in Practice	TYPICAL TECHNOLOGY
POC	1. *n/d* 2. *Enclosure of photoresist track and spinner, and vent to abatement system w/ destruction/recovery efficiency ≥98.5% or VOC outlet concentration ≤10 ppmv*[a,b,T]	1. *n/d* 2. *BAAQMD approved Collection System and Abatement Device*[a,b,T]
NOx	1. *n/a* 2. *n/a*	1. *n/a* 2. *n/a*
SO_2	1. *n/a* 2. *n/a*	1. *n/a* 2. *n/a*
CO	1. *n/a* 2. *n/a*	1. *n/a* 2. *n/a*
PM_{10}	1. *n/a* 2. *n/a*	1. *n/a* 2. *n/a*
NPOC	1. *n/d* 2. *Same as for POC above*[a,b,T]	1. *n/d* 2. *BAAQMD approved Collection system and Abatement Device*[a,b,T]

References

a. BAAQMD A #6266
b. For abatement device, the following are acceptable: ≤10 ppmv at outlet; or ≥98.5% destruction/recovery efficiency if inlet VOC ≥2000 ppmv: or ≥97% efficiency if inlet VOC ≥200 to <2000 ppmv; or ≥90% efficiency if inlet VOC <200 ppmv.
T. TBACT